

FORM PTO-1449 (Modified) LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT	ATTY. DOCKET NO. YOR920000344US1	SERIAL NO.: 09/692,606
	APPLICANT: Jack O. Chu et al.	
	FILING DATE: October 19, 2000	GROUP: 1765

REFERENCE DESIGNATION**U.S. PATENT DOCUMENTS**

EXAMINE R INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPRO.)
EK	AA	6,059,895	05/09/2000	Chu et al.	148	33.1	May 13, 1999
EK	AB	5,650,353	07/22/1997	Yoshizawa et al.	437	62	November 21, 1995
EK	AC	5,240,876	08/31/1993	Gaul et al.	437	131	June 1, 1992
	AD						
	AE						
	AF						

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FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
CK	AG	WO 99/53539	10/21/1999		H01L	21/306		
AH								
AI								
AJ								

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OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

Ak	XP-002111024, "Epitaxial Si-Ge Etch Stop Layers With Ethylene Diamine Pyrocatechol For Bonded And Etchback Silicon-On-Insulator", D. Feijoo et al., AT&T Bell Laboratories, Murray Hill, NJ 07974, revised February 2, 1994.
AM	

EXAMINER *Eric K. Chu***DATE CONSIDERED** *7/15/03*

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.